

# Neutron detection characterization for B GaN neutron semiconductor imaging sensors

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Recently, neutron detection has been applied in various fields, and the development of neutron detectors that are suitable for widespread neutron detection is expected. B GaN has been proposed and developed as a novel neutron semiconductor detection material. B GaN is a ternary nitride alloy that includes B atoms, and is capable of capturing neutrons and detecting signals in a sensitive layer. Such B GaN detectors have been developed as neutron-detecting semiconductors capable of pseudo-direct detection. B GaN has been developed as a UV LED semiconductor material, but is not currently being developed due to the difficulty of B GaN epitaxial growth. We have developed B GaN epitaxial growth using metal-organic vapor phase epitaxy (MOVPE) for B GaN to function as a neutron-detecting semiconductor, and have achieved the establishment of thick film epitaxial growth technique[1]. Furthermore, the fabrication of a pin diode structure and neutron detection was achieved, indicating the possibility of a B GaN neutron detector[2]. However, sufficient neutron detection characteristics have not been obtained, and understanding the detailed neutron detection behavior in B GaN detectors is important for future development. However, the neutron detection characteristics are not enough, and the understanding of the neutron detection mechanism in B GaN detectors is important for future development. Therefore, B GaN neutron detection characteristics are evaluated by the results of irradiation experiments using monochromatic neutrons and calculation results using PHITS code to obtain a direction toward a neutron imaging sensor.

We fabricated pin-B GaN diodes by using metal organic chemical vapor deposition (MOCVD). Growth conditions in MOCVD are described in the following. Ga, B and N source gases are TMGa, TMB and NH<sub>3</sub>, respectively. The Mg and Si dopants were used Cp<sub>2</sub>Mg and MMSi. 10-

μm-B GaN layers were grown under nitrogen atmosphere at a growth temperature of 1000 °C and a growth pressure of 10 kPa. Structure characteristics for B GaN films are evaluated by X-ray diffraction (XRD) and scanning electron (SEM) measurement. Radiation detection characteristics for B GaN detectors are evaluated by energy spectra measurement for each radiation source. <sup>241</sup>Am was used in the α-particles irradiation experiment. Neutron irradiation experiments were conducted at MINE-1 in Japan Research Reactor 3 (JRR-3).

Figure 1 shows the energy spectra of 10 μm-B GaN devices under irradiation of neutron and α-particles. As a result, the neutron detection peak was confirmed. The neutron capture peak was obtained for the first time in neutron detection using a B GaN detector, confirming that the B GaN detector is detecting neutrons. The peak profile (peak position and FWHM value) was slightly changed compared to the 2.3 MeV α-particle energy spectrum. We are considering the effect of charged particles escaping outside the sensitive layer as the reason of this difference. However, further studies are needed to elucidate the details.

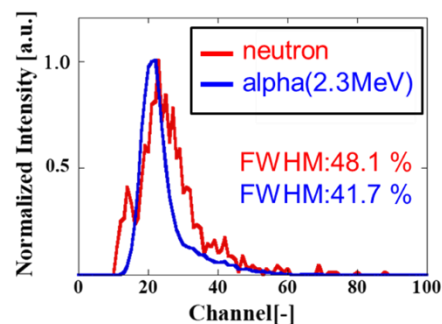


Fig 1. energy spectra of B GaN devices under irradiation of neutron and α particles

[1] K. Ebara *et al.*, Jpn. J. Appl. Phys. **58**, SC1042 (2019)

[2] T. Nakano *et al.*, J. Appl. Phys. **130**, 124501 (2021)